

ABSTRACT

A chemical amplification type resist composition
5 comprising a specific benzenesulfonyldiazomethane containing
a long-chain alkoxy group at the 2-position on benzene ring
has many advantages including improved resolution, improved
focus latitude, minimized line width variation or shape
degradation even on long-term PED, minimized debris left
10 after coating, development and peeling, and improved pattern
profile after development and is thus suited for
microfabrication.